




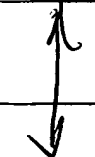



Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No. KLA1P119	Application No.: 10/760,149
	Applicant: Mieher et al.	
	Filing Date January 17, 2004	Group 2877

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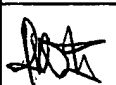





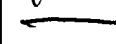
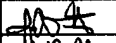
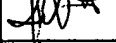
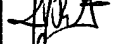


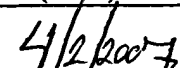
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Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.